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Structural and electro-optic properties of laser ablated $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ thin films on $\text{SrTiO}_3(100)$ and $\text{SrTiO}_3(110)$

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$\text{Bi}_4\text{Ti}_3\text{O}_{12}$ thin films have been grown by laser ablation on $\text{SrTiO}_3(100)$ and $\text{SrTiO}_3(110)$ substrates. Substrate surface orientation is found to be an important growth parameter which determines crystal axis orientation, grain growth behavior, and electro-optic properties of the $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ thin films. The films grown on $\text{SrTiO}_3(110)$ shows a ferroelectric phase transition near 720°C and a large quadratic electro-optic effect with the effective coefficient $1.1 \times 10^{-16} \text{ m}^2/\text{V}^2$.

$\text{Bi}_4\text{Ti}_3\text{O}_{12}$ is an interesting ferroelectric material with useful properties for nonvolatile memory, piezoelectric, and electro-optic devices.¹ Recently, epitaxial $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ thin films have been successfully grown by pulsed excimer laser deposition on $\text{SrTiO}_3(100)$,² $\text{MgO}(110)$,³ and $\text{YBa}_2\text{Cu}_3\text{O}_7(001)$.⁴ The feasibility for growing lattice-matched heterostructures makes this material very attractive for several applications. In this letter we report effects of substrate surface orientation, i.e., (100) and (110) faces of SrTiO_3 single crystal, on structural and electro-optic properties of the laser ablated $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ films.

A visible laser, i.e., second harmonics (532 nm) of a Q-switched Nd:YAG laser, was used in this study instead of commonly used ultraviolet lasers.²⁻⁴ The laser was pulsed at a rate of 20 Hz, and the beam was focused with a quartz lens onto a polycrystalline, single-phase $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ target. Fluence of the beam on the target was estimated to be $1.5\text{--}2 \text{ J/cm}^2$. Thin-film deposition was carried on a single-crystal substrate, $\text{SrTiO}_3(100)$ or $\text{SrTiO}_3(110)$, which was maintained at temperature of $730\text{--}750^\circ\text{C}$ in oxygen atmosphere of 200 mTorr. After the deposition, the thin films were *in situ* annealed at 500°C in oxygen atmosphere of 500 Torr for 30 min. They were characterized using x-ray diffractometry methods (2θ scan, rocking curve, and x-ray pole figure) and scanning electron microscopy (SEM). Their linear birefringences were also measured as a function of temperature and dc electric field.

X-ray diffraction patterns are shown in Fig. 1. The pattern of the $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ thin film on $\text{SrTiO}_3(100)$, as shown in Fig. 1(a), has only (00 l) peaks in agreement with an earlier report.² The rocking curve full width at half maximum (FWHM) is about 0.3° for the (006) peak of the film. This value informs us that grains are well aligned with their c -axes normal to the substrate. However, the film on $\text{SrTiO}_3(110)$ shows a (117) peak as well as (00 l) peaks, as shown in Fig. 1(b). This result indicates that this film is composed of grains with more than one orientation.

A relation between the crystal axes of $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ and the in-plane vectors of SrTiO_3 can be obtained using x-ray pole figure. The Schultz geometry⁵ was used in this measurement. The α and β rotations are coupled so that a 360° rotation of β corresponds to a 2.5° decrease of α . (The 2θ scan corresponds to $\alpha=90^\circ$.) As shown in Fig. 2(a), the four (117) reflections of the film on $\text{SrTiO}_3(100)$ are lo-

cated at $\beta=0^\circ, 90^\circ, 180^\circ$, and 270° with $\alpha \cong 40^\circ$. This indicates that the [117] direction of the $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ grains is aligned in the ac -plane of SrTiO_3 lattice with the polar angle of about 50° from the c -axis of the substrate. This epitaxial growth behavior can be understood from the fact that the lattice constants of $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ ($a=5.448 \text{ \AA}$ and $b=5.410 \text{ \AA}$) are close to the length of the face diagonal of the SrTiO_3 lattice ($a=3.905 \text{ \AA}$ for SrTiO_3).

Figure 2(b) shows a pole figure of the film on $\text{SrTiO}_3(110)$ for (117) and (008) reflections of $\text{Bi}_4\text{Ti}_3\text{O}_{12}$. Similar to Fig. 2(a) the resulting (117) reflections, which come from the grains with their c -axes normal to the substrate, have fourfold azimuthal orientations along the [100] and [110] directions of the substrate. This tendency can be understood from the fact that the lattice constant of SrTiO_3 along the [110] direction is very close to that of $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ along a -axis. On the other hand, the (008) reflections show strong peaks at $\beta \cong 20^\circ$ and 200° with $\alpha \cong 40^\circ\text{--}48^\circ$. These reflections come from the grains with their (117) planes nearly parallel to the substrate. Most of these grains are

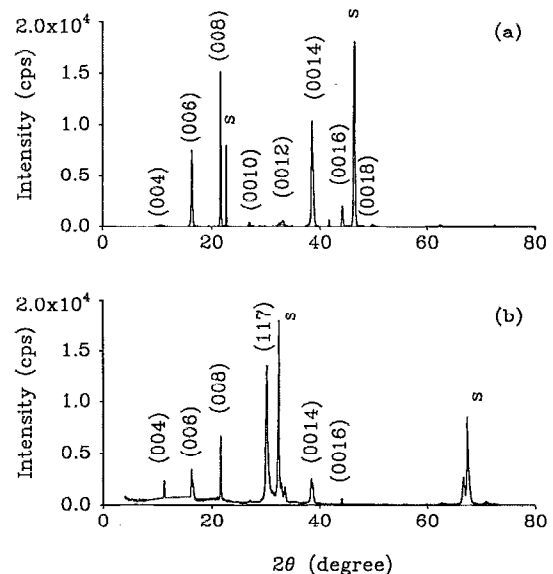


FIG. 1. X-ray diffraction patterns of $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ thin films on (a) $\text{SrTiO}_3(100)$ and (b) $\text{SrTiO}_3(110)$. The character "s" indicates peaks of SrTiO_3 .

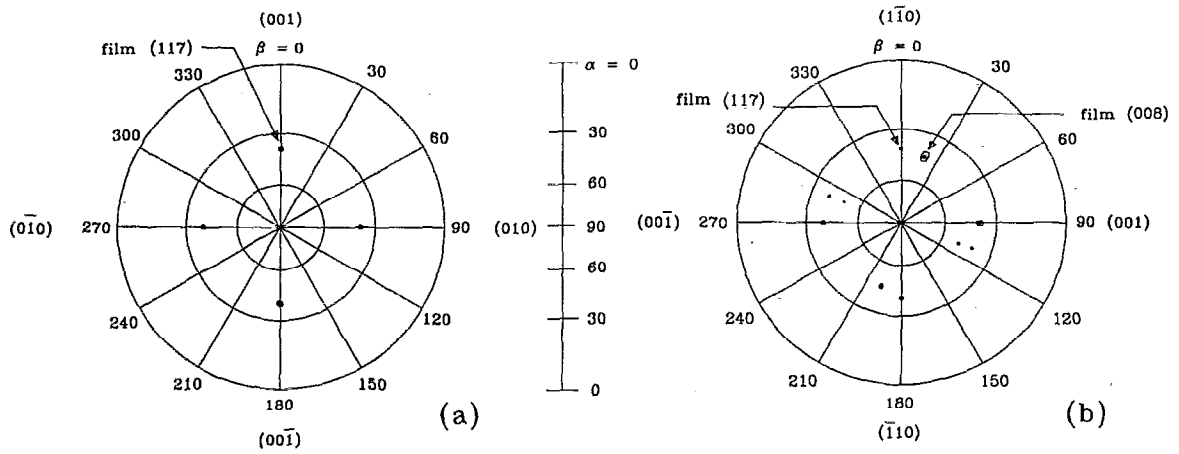


FIG. 2. X-ray pole figures of $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ thin films on (a) $\text{SrTiO}_3(100)$ and (b) $\text{SrTiO}_3(110)$.

oriented along an angle of 20° from $[1\bar{1}0]$ direction of SrTiO_3 and an angle around 46° from the normal direction of the SrTiO_3 substrate. Therefore, the film on $\text{SrTiO}_3(110)$ is composed of grains which are highly oriented along some directions.

SEM micrographs, shown in Fig. 3, also demonstrate an interesting difference in grain growth behavior between the $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ thin films. The film on $\text{SrTiO}_3(100)$ shows grain growth without any preferred habit but the film on $\text{SrTiO}_3(110)$ shows growth of elliptical grains which are aligned along a direction about 20° away from the $[110]$ direction of the substrate. This tilt angle is similar to that of the strongest (008) peaks in Fig. 2(b). Therefore, the SrTiO_3 surface orientation influences grain growth behavior as well as crystal axis orientation.

Linear birefringence, Δn , was measured by the Senarmont method⁶ using a 15 mW He-Ne laser. For a thin film of 5000 Å thickness, the resolution of Δn in our system was about 10^{-4} . Birefringence of a blank SrTiO_3 substrate was

measured separately and showed no significant shift within our experimental error. For the temperature dependence measurement, the samples were heated with a furnace. For the electric field dependence measurement, silver electrodes were thermally evaporated on a thin film with a separation of 0.5 mm. A dc electric field up to 20 kV/cm was applied parallel to the $[1\bar{1}0]$ direction of the $\text{SrTiO}_3(110)$ substrate. The light enters with its polarization at an angle of 45° with respect to the direction of the electric field.

Figure 4(a) shows the temperature dependent birefringences for the $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ thin films. The birefringence of the film on $\text{SrTiO}_3(100)$, $\Delta n_{(100)}$, is similar to that of a single-crystal $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ when the light enters the crystal along the c -axis.⁷ The birefringence of the film on $\text{SrTiO}_3(110)$, $\Delta n_{(110)}$, is much larger than $\Delta n_{(100)}$, and the former comes from the contribution of Δn 's along three

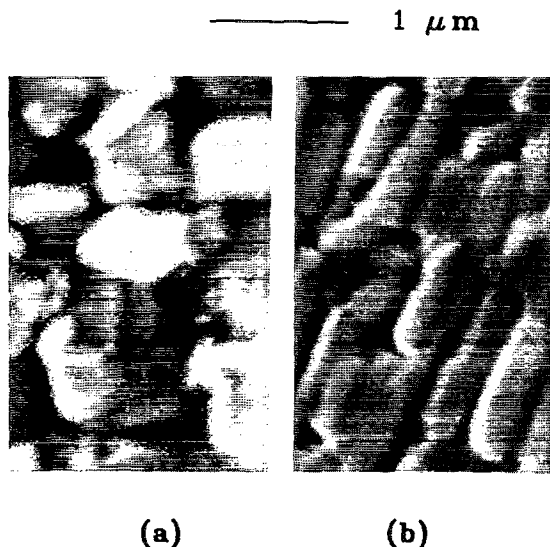


FIG. 3. Scanning electron micrographs of $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ thin films on (a) on $\text{SrTiO}_3(100)$ and (b) $\text{SrTiO}_3(110)$.

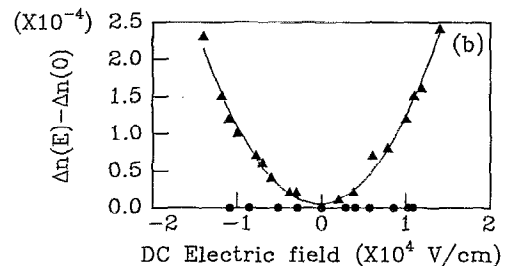
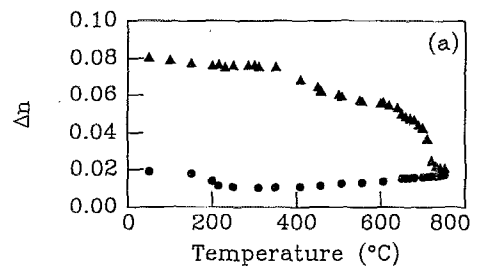


FIG. 4. (a) Temperature dependence of linear birefringence shift, Δn , of $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ thin films. (b) Changes in Δn as a function of applied electric field. In these figures, solid circles represent the data for the film on $\text{SrTiO}_3(100)$ and solid triangles represent those on $\text{SrTiO}_3(110)$.

crystal axes.⁷ An abrupt change in $\Delta n_{(110)}$, which is related to the ferroelectric transition, is observed near 720 °C. This Curie temperature is higher than that of a single crystal, i.e., 676 °C.⁷ A similar shift of 50 °C in the Curie temperature was reported for the epitaxial PbTiO_3 thin films,⁸ and it was interpreted as a stress induced shift.⁹

Figure 4(b) shows changes in Δn , i.e., $\Delta n(E) - \Delta n(E=0)$, as a function of applied electric field E . Little changes in Δn are observed for the thin film on $\text{SrTiO}_3(100)$. However, the film on $\text{SrTiO}_3(110)$ shows very large changes in Δn which can be fitted to a quadratic equation of E . The linear electro-optic component is found to be very small and that is in agreement with the fact that our measured Δn 's are the average responses from the multidomain material.¹⁰ The effective quadratic electro-optic coefficient is calculated to be $1.1 \times 10^{-16} \text{ m}^2/\text{V}^2$. This value is larger than those of most ferroelectric films [typically, 10^{-17} – $10^{-19} \text{ m}^2/\text{V}^2$ for $(\text{Sr},\text{Ba})\text{Nb}_2\text{O}_6$, BaTiO_3 , and $\text{Ba}_2\text{NaNb}_5\text{O}_{15}$],¹¹ and it is also larger than that of sputtered $(\text{Pb},\text{La})(\text{Zr},\text{Ti})\text{O}_3$ thin film [i.e., $4.43 \times 10^{-17} \text{ m}^2/\text{V}^2$] by a factor of 2.¹¹ Therefore, the $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ film on $\text{SrTiO}_3(110)$ is a good candidate material for the electro-optic device applications.

In summary, $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ thin films have been grown on $\text{SrTiO}_3(100)$ and $\text{SrTiO}_3(110)$ by laser ablation. From x-ray diffraction SEM and linear birefringence measurements, it is found that the SrTiO_3 surface orientation determines crystal axis orientation, grain growth behavior,

and electro-optic properties of the $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ thin films. A ferroelectric phase transition is observed near 720 °C, which is higher than the transition temperature of a bulk $\text{Bi}_4\text{Ti}_3\text{O}_{12}$. The effective quadratic electro-optic coefficient for the film grown on $\text{SrTiO}_3(110)$ is evaluated to be $1.1 \times 10^{-16} \text{ m}^2/\text{V}^2$.

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